

Slow crack growth behavior in Si_3N_4 sintered with $\text{Yb}_2\text{Si}_2\text{O}_7$ tie-line composition additives

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Abstract

Slow crack growth behavior of two gas pressure sintered Si_3N_4 ceramics with different additives; a $\text{Yb}_2\text{Si}_2\text{O}_7$ composition and an $\text{Al}_2\text{O}_3\text{--Y}_2\text{O}_3$ composition, was investigated by constant stress-rate (“dynamic fatigue”) testing at 1400°C . The slow crack growth parameter, n , was 14.7 and 6.3 for Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ and $\text{Al}_2\text{O}_3\text{--Y}_2\text{O}_3$ compositions, respectively. Superior crack growth resistance of Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ composition was due to its higher refractoriness of intergranular glassy films, compared to Si_3N_4 with $\text{Al}_2\text{O}_3\text{--Y}_2\text{O}_3$ composition. © 2001 Elsevier Science Ltd. All rights reserved.

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1. Introduction

Si_3N_4 ceramics are densified by liquid phase sintering using metal oxides as sintering additives. The oxides form an oxynitride melt during sintering and remain at grain boundary as an intergranular glassy film (IGF) after sintering. Presence of the residual IGF leads to the degradation of high temperature properties.^{1,2} Several attempts to optimize high temperature properties have been investigated, including the crystallization of the IGF by a post heat treatment,³ the formation of a transient liquid phase sintering,⁴ and the reduction of the overall additive content in combination with the use of refractive additives.^{5,6}

Work performed by Lange et al.⁷ on the $\text{Si}_3\text{N}_4\text{--SiO}_2\text{--Y}_2\text{O}_3$ system has shown that the high temperature properties of Si_3N_4 can be improved by choosing compositions in the $\text{Si}_3\text{N}_4\text{--Si}_2\text{N}_2\text{O--Y}_2\text{Si}_2\text{O}_7$ compatibility triangle, since the $\text{Si}_2\text{N}_2\text{O}$ and $\text{Y}_2\text{Si}_2\text{O}_7$ phases are in equilibrium with SiO_2 , the oxidation product of Si_3N_4 . Lange⁸ also proposed similar behavior for compositions in the $\text{Si}_3\text{N}_4\text{--SiO}_2\text{--CeO}_2$ system. On this basis, various rare-earth oxides have been studied as potential sinter-

ing additives and verified as effective as Y_2O_3 in the densification of Si_3N_4 .^{3,9,10} Furthermore, refractory disilicate, $\text{Re}_2\text{Si}_2\text{O}_7$ (Re refers to the cation of a rare earth oxide), can be crystallized at grain boundaries, thereby resulting in improved high temperature properties.^{3,11–13} These results make the $\text{Si}_3\text{N}_4\text{--Re}_2\text{Si}_2\text{O}_7$ tie-line composition attractive for high temperature application of Si_3N_4 .

Among the $\text{Si}_3\text{N}_4\text{--SiO}_2\text{--Re}_2\text{O}_3$ systems, we have shown that $\text{Si}_3\text{N}_4\text{--Yb}_2\text{Si}_2\text{O}_7$ composition is one of the best candidates for better high temperature application because of its good flexural strength and oxidation resistance.^{14,15} In this study, we characterized slow crack growth (SCG) behavior, that is important to estimate the service life at elevated temperatures, of Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ composition by using constant stress-rate (“dynamic fatigue”) testing at 1400°C and compared to that of Si_3N_4 with 2 wt.% $\text{Al}_2\text{O}_3\text{--4 wt.% Y}_2\text{O}_3$ composition.

2. Experimental procedure

Commercially available Si_3N_4 (SN E-10, Ube Industries, Tokyo, Japan), Yb_2O_3 , Y_2O_3 (99.9%, Johnson Matthey, Seabrook, NH, USA), SiO_2 (99.9%, Aerosil 200, Degussa Co., NJ, USA), and Al_2O_3 (99.99%, AKP 30, Sumitomo Chemicals, Tokyo, Japan) powders were

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used as starting materials. Two compositions, designated as SNYb and SNAY, were prepared corresponding to Si_3N_4 (94 wt.%)– Yb_2O_3 (4.6 wt.%)– SiO_2 (1.4 wt.%) and Si_3N_4 (94 wt.%)– Y_2O_3 (4 wt.%)– Al_2O_3 (2 wt.%), respectively. The composition of SNYb corresponds to the Si_3N_4 – $\text{Yb}_2\text{Si}_2\text{O}_7$ tie line.¹⁴ The powder mixtures were milled in methanol for 24 h using Si_3N_4 balls. The milled slurry was dried, sieved, and gas pressure sintered at 1750°C for 2 h under 12 MPa of nitrogen pressure and subsequently annealed at 1950°C for 4 h under 30 MPa of nitrogen pressure.

Densities were measured using Archimedes method. The theoretical densities of the specimens were calculated according to the rule of mixtures. X-ray diffractometry (XRD) was used for ground powders. The sintered specimens were cut, polished, and then plasma-etched by CF_4 containing 7.8% O_2 . The microstructures were observed by scanning electron microscopy (SEM). Thin foils for high resolution transmission electron microscopy (HRTEM, Philips CM30, Eindhoven, The Netherlands) were prepared by the standard procedures of grinding, dimpling, and ion-beam thinning followed

by carbon coating to minimize charging during the observation of IGF.

Specimens for SCG tests were cut and polished to rectangular bars in a dimension of 3×4×25 mm. Constant stress-rate testing was performed using three-point bend fixture with a span of 15 mm at 1400°C in air. Five or six different speed rates from 10⁻² to 10³ MPa/s were employed using a position-controlled mode. A total of ~50 specimens for each composition was tested and the average data obtained from the five specimens were used for the subsequent SCG analysis as described in ASTM standard C 1368.

3. Results and discussion

Relative densities of higher than 98% were obtained for both SNYb and SNAY. SEM micrographs of polished and etched surfaces are shown in Fig. 1. As shown, both have a typical in situ toughened microstructure of Si_3N_4 .¹⁶ Fig. 2 shows the XRD analysis of SNYb and SNAY. It shows that the secondary crystalline phase for SNYb is $\text{Yb}_4\text{Si}_2\text{N}_2\text{O}_7$, which is not the expected compound in the Si_3N_4 – $\text{Yb}_2\text{Si}_2\text{O}_7$ tie-line composition, however, is the compound in the Si_3N_4 – $\text{Yb}_4\text{Si}_2\text{N}_2\text{O}_7$ tie-line composition.¹⁷ Earlier study¹⁴ showed that hot-pressing with this composition results in $\text{Yb}_2\text{Si}_2\text{O}_7$ as secondary crystalline phase. This difference seems to be originated from the high nitrogen pressure (30 MPa in this study) during sintering, which increases the solubility of nitrogen for the liquid phase. The solubility of nitrogen decreases with decreasing temperature and, therefore, the dissolved nitrogen may participate into the formation of a crystalline phase during cooling. In contrast, a secondary crystalline phase is not detected for SNAY, which indicates that crystallization has not readily occurred in SNAY composition.

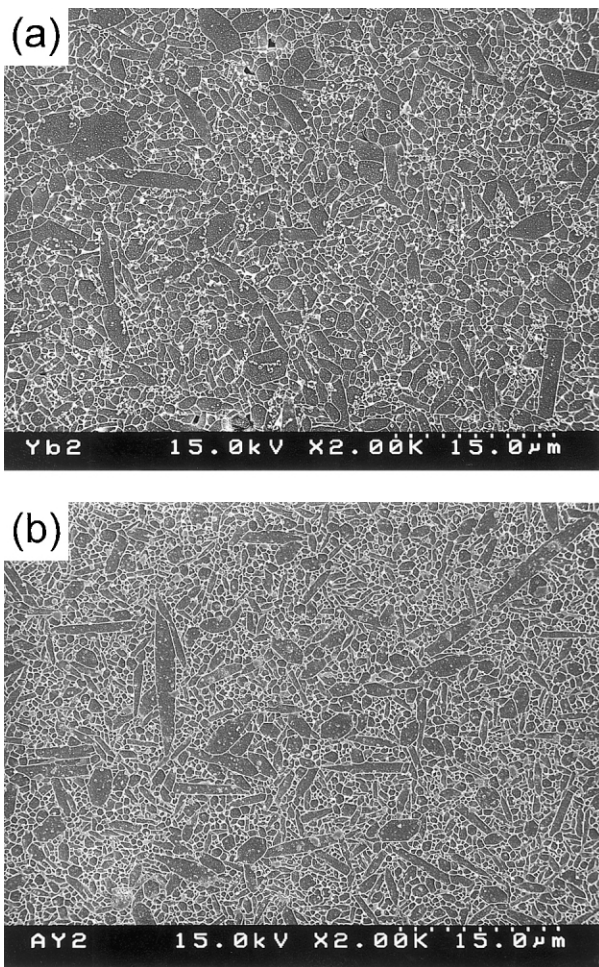


Fig. 1. Typical microstructures for (a) Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ composition and (b) Si_3N_4 with 2 wt.% Al_2O_3 and 4 wt.% Y_2O_3 .

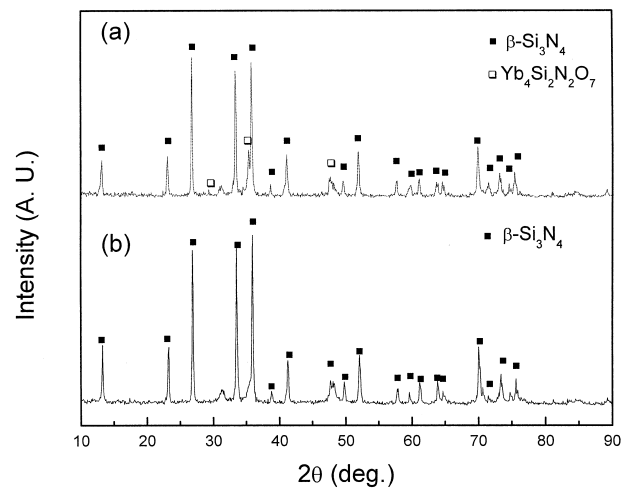


Fig. 2. XRD patterns for (a) Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ composition and (b) Si_3N_4 with 2 wt.% Al_2O_3 and 4 wt.% Y_2O_3 .

The results of constant stress-rate testing for SNYb and SNAY at 1400°C are shown in Fig. 3, where $\log \sigma_f$ (fracture strength) was plotted as a function of $\log \dot{\sigma}$ (stress rate). The room temperature strengths were arbitrarily plotted for comparison at $\dot{\sigma} = 10^4$ MPa/s. Both SNYb and SNAY exhibited an increase in strength with stress rate. The value of SCG parameter, n , for SNYb and SNAY was determined by a linear regression analysis using the mean strength data. The resulting n was 14.7 and 6.3 for SNYb and SNAY, respectively. To better represent the strength degradation, the strengths at 1400°C were normalized with respect to the corresponding room temperature strength, to give a reduced strength, σ_r . The σ_r is defined as follows:¹⁸

$$\sigma_r = \frac{\sigma_{f/HT}}{\sigma_{f/RT}} \quad (1)$$

where $\sigma_{f/HT}$ and $\sigma_{f/RT}$ are elevated and room-temperature strengths, respectively. The resulting plot of $\log \sigma_r$ as a function of $\log \dot{\sigma}$ is shown in Fig. 4. It indicates that the strength increases from the slow stress test rate (of the order of 10^{-2} MPa/s) to fast stress rate (of the order of 10^3 MPa/s). σ_r increased from 0.29 to 0.55 for SNYb (90% increased) and from 0.10 to 0.31 for SNAY (210% increased). Figs. 3 and 4 indicate that SNYb has better slow crack growth resistance than SNAY.

The elevated-temperature slow crack growth was known as a rate-dependent process occurring by viscous flow of the IGF.^{19,20} The viscous flow behavior of IGF is predominantly determined by its refractoriness. The refractory nature can be estimated from the eutectic temperature of sintering additive oxide–SiO₂ system^{11,12} and cationic size of sintering additives if the cation act as a network modifier in the SiO⁻⁴ network structure of IGF.^{14,15} The eutectic temperature of the Yb₂O₃–SiO₂

system (1650°C) is higher than that of the Al₂O₃–Y₂O₃–SiO₂ system (<1505°C). The ionic radius of Yb³⁺ (0.985×10^{-1} nm) is smaller than that of Y³⁺ (1.011×10^{-1} nm) (The ionic radius of Al³⁺, 0.390×10^{-1} nm, is much smaller than that of Yb³⁺ and, therefore, more refractory nature could be expected with addition of Al₂O₃. However, unlikely Yb³⁺ or Y³⁺, Al³⁺ is incorporated not as modifier but as network former in the IGF structure and greatly weakens the structure and refractoriness). Therefore, the more refractory nature of IGF could be expected for SNYb.

A tie-line composition could also contribute to the refractory nature of IGF for SNYb. A recent study on the diffusive interface description of IGF indicates that there is a “chemical” driving force, which depends on the difference in solute concentration between the liquid phase and the crystalline Si₃N₄ phase, reducing the thickness of IGF and, ultimately, depleting of the IGF in the selective compositions.²¹ It has also been reported that the creep resistance, which is also a rate-dependent process occurring by viscous flow of the IGF, of Si₃N₄ ceramics is high when the composition is at the tie-line.¹¹ Since the creep resistance is mainly controlled by the presence of IGF, it may show a maximum when the grain boundaries are free of IGF. This means that a strong chemical driving force, which can exclude the effect of IGF on the high temperature properties, could be expected at the tie-line composition. Furthermore, readily crystallization of a secondary crystalline phase at triple-junctions, which contributes to better refractoriness of IGF, and high temperature properties can be expected at the tie-line composition.^{3,11,12}

Fig. 5 shows the IGF of SNYb and SNAY observed by HRTEM. The IGF for SNYb is narrower (~ 1 nm) compared to that of SNAY (~ 1.5 nm). It may be due to the following two factors: (1) the chemical driving force

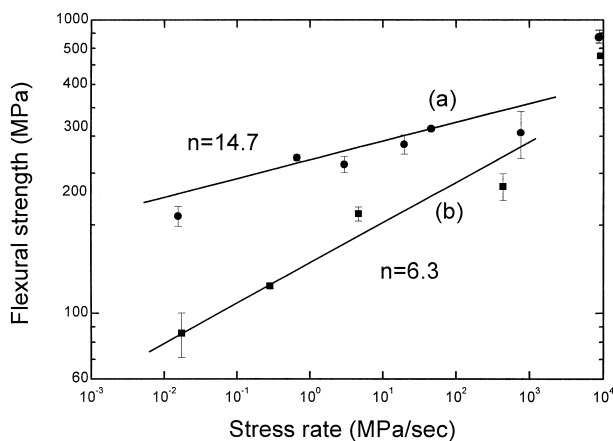


Fig. 3. Plots of 1400°C strength (σ_f) vs stress rate ($\dot{\sigma}$) for (a) Si₃N₄ with Yb₂Si₂O₇ composition and (b) Si₃N₄ with 2 wt.% Al₂O₃ and 4 wt.% Y₂O₃. The room temperature strengths were arbitrarily plotted at $\dot{\sigma} = 10^4$.

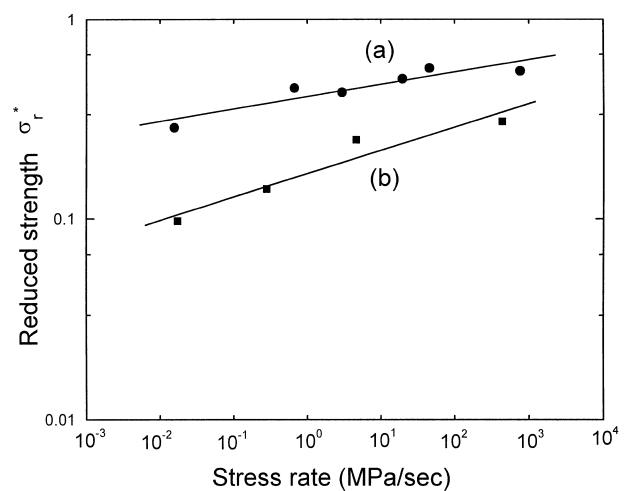


Fig. 4. Plots of reduced strength (σ_r) vs stress rate ($\dot{\sigma}$) for (a) Si₃N₄ with Yb₂Si₂O₇ composition and (b) Si₃N₄ with 2 wt.% Al₂O₃ and 4 wt.% Y₂O₃.

for SNYb is stronger than that of SNAY since it has at tie-line composition; (2) most Al^{3+} and Y^{3+} ions may be remained in the IGF since secondary phase containing both ions is not readily crystallized for SNAY. In contrast, the $\text{Yb}_4\text{Si}_2\text{N}_2\text{O}_7$ phase is readily crystallized (Fig. 2), which means that most of the Yb^{3+} ions are incorporated in the formation of a crystalline phase. It can contribute to the narrow IGF thickness since the cations of sintering additives widen the thickness of IGF.²² The two factors contribute to a narrow thickness of IGF also contribute to the superior refractory nature of IGF and better slow crack growth resistance since the former excludes the effect of IGF on the high temperature and the latter results in a silica-rich composition of IGF that has superior refractory nature.²³

4. Summary

Slow crack growth behavior of two kinds of Si_3N_4 ceramics using constant stress rate testing showed that Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ tie-line composition as sintering additives has better slow crack growth resistance, compared to Si_3N_4 with $\text{Al}_2\text{O}_3\text{-Y}_2\text{O}_3$ composition as sintering additives. It was inferred that (i) high eutectic temperature of $\text{Yb}_2\text{O}_3\text{-SiO}_2$ system, (ii) small cationic radius of Yb^{3+} ion, (iii) strong “chemical driving force” at tie-line composition and (iv) easy crystallization of Yb-containing secondary crystalline phase may contribute to the highly refractory nature of the intergranular glassy film and result in better resistance to slow crack growth.

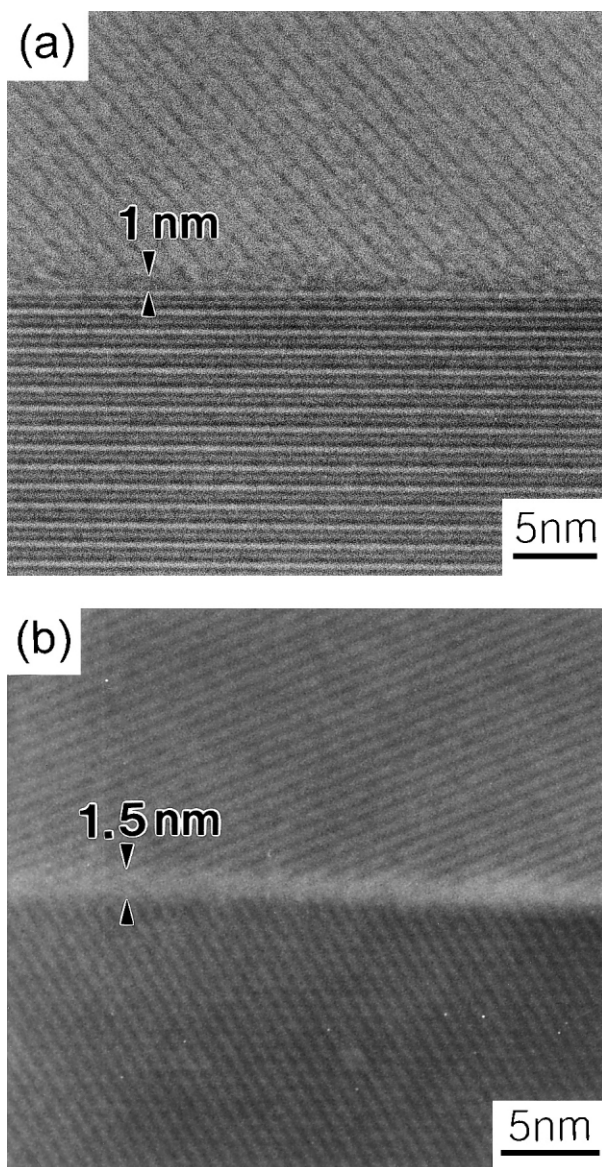


Fig. 5. Representative HRTEM micrographs of grain boundaries for (a) Si_3N_4 with $\text{Yb}_2\text{Si}_2\text{O}_7$ composition and (b) Si_3N_4 with 2 wt.% Al_2O_3 and 4 wt.% Y_2O_3 .

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